

MANUFACTURING METHOD OF PHOTOMASK, AND PHOTOMASK BLANK

ABSTRACT

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A photomask is manufactured from a photomask blank including a transparent substrate, a first inorganic film which comprises silicon and is free of chromium, and a second inorganic film which comprises chromium and is free of silicon, and is in contact with the first inorganic film by a method including steps of forming a pattern of the second
10 inorganic film by fluorine-based dry etching with using a resist pattern, and forming a pattern of the first inorganic film by fluorine -based dry etching with using the pattern of the second inorganic film.

[Figure 1]